

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently amended) Method for producing a grating image (16, 19), which at least has one grating field (6, 61, 62, 63, 64, 65, 66), comprising the following steps:
 - defining a contour line (9) of the grating field (6, 61, 62, 63, 64, 65, 66),
 - filling the contour line (9) with the grating pattern (10), the grating pattern (10) within the contour line (9) being described by grating coordinates,
 - supplying the grating coordinates to a writing apparatus and
 - producing the grating pattern (10) in a substrate with the writing apparatus and with the help of the grating coordinates.
2. (Currently Amended) Method according to claim 1, **characterized in that** the grating pattern (10) is formed by grating lines (13) which are disposed side by side.
3. (Currently Amended) Method according to claim 2, **characterized in that** as grating coordinates are selected the intersection points, the grating lines (13) have with the contour line (9), lying within the contour line.
4. (Currently Amended) Method according to claim 1, **characterized in that** with the help of a data processing system the contour line of the grating field (6, 61, 62, 63, 64, 65, 66) is created and filled with the grating pattern (10).
5. (Previously Presented) Method according to claim 1, **characterized in that** the grating lines are straight or curved.

6. (Currently Amended) Method according to claim 1, **characterized in that** the grating coordinates of the grating lines (13) are sequentially sorted according to their spatial disposition.
7. (Currently Amended) Method according to claim 6, **characterized in that** the coordinates of a starting point (14) of a grating line (13) are sorted side by side with the respective coordinates of a starting point (14) of a neighboring grating line (13) and the coordinates of an end point (15) of a grating line (13) side by side with the respective coordinates of an end point (15) of a further neighboring grating line (13).
8. (Currently Amended) Method according to claim 7, **characterized in that** the starting points and end points of grating lines (13) located side by side are connected to form a meandering processing path (17).
9. (Previously presented) Method according to claim 1, **characterized in that** the writing apparatus with the help of radiation causes a change of state in a radiation-sensitive material.
10. (Original) Method according to claim 9, **characterized in that** the writing apparatus is guided over the radiation-sensitive material according to the grating coordinates.
11. (Previously Presented) Method according to claim 9, **characterized in that** as a radiation-sensitive material a photoresist layer applied onto a substrate plate is used.
12. (Previously Presented) Method according to claim 1, **characterized in that** as a writing apparatus an electron beam is used.
13. (Currently Amended) Method according to claim 19, **characterized in that**

after the caused change of state a metallization layer is applied onto the radiation-sensitive material and that therefrom a metallic molding is galvanically produced.

14. (Original) Method according to claim 13, **characterized in that** the molding is used as an embossing die for embossing a grating image into a substrate.
15. (Original) Grating image, which has at least one image field separately perceptible with the naked eye, in which a grating pattern consisting of not interrupted grating lines is disposed, which is produced by means of a lithography instrument.
16. (Previously Presented) Grating image according to claim 15, **characterized in that** as a lithography instrument focussed light radiation or a focussed particle beam, is used.
17. (Previously Presented) Grating image according to claim 15, **characterized in that** the grating image has several image fields.
18. (Previously Presented) Grating image according to claim 15, **characterized in that** the grating image has further image parts, which are manufactured with the help of a different technique.
19. (Previously Presented) Grating image, according to claim 15, **characterized in that** the grating pattern comprises grating lines, which form a diffraction grating.
20. (Currently Amended) Grating image according to claim 15, **characterized in that** the grating lines (13) are connected to at least one meandering grating line by reversing sections (23) disposed at their ends (14, 15).
21. (Currently Amended) Grating image according to claim 15, **characterized in**

that the reversing distances (23) are rounded.

22. (Previously Presented) Security element with a grating image according to claim 15.
23. (Original) Security element according to claim 22, **characterized in that** the security element is a security thread, a label or a transfer element.
24. (Previously Presented) Security paper with a grating image according to claim 15.
25. (Previously Presented) Security paper with a security element according to claim 22.
26. (Previously Presented) Security document with a grating image according to claim 15.
27. (Previously Presented) Security document with a security element according to claim 22.
28. (Previously Presented) Security document with a security paper according to claim 24.
29. (Previously Presented) Transfer material with a grating image according to claim 15.
30. (Original) Apparatus for producing a grating image, which at least has one grating field perceptible with the naked eye, comprising the following devices:
 - device for defining a contour line of the grating field,
 - device for filling the contour line with a grating pattern, the grating pattern being described within the contour line by grating coordinates,
 - device for supplying the grating coordinates to a writing apparatus,

- writing apparatus for producing the grating pattern in a substrate with the help of the grating coordinates.

31. (Original) Apparatus according to claim 30, **characterized in that** the writing apparatus is an electron beam.

32. (Previously Presented) The method of claim 3 wherein the grating points of the grating field lie within the contour line.

33. (Previously Presented) The grating image of claim 16 wherein said particle beam is an electron beam.

34. (Previously Presented) A security paper with a security element according to claim 23.

35. (Previously Presented) A security document with a security element according to claim 23.

36. (Previously Presented) A security document with a security paper according to claim 25.

37. (Previously Presented) The transfer material of claim 29, comprising hot stamping foil.